# ISO 14706:2014-08 (E)

## Surface chemical analysis - Determination of surface elemental contamination on silicon wafers by total-reflectio n X-ray fluorescence (TXRF) spectroscopy

## Contents

Page


Foreword ..... iv

Introduction ..... v

1 Scope ..... 1

2 Normative reference ..... 1

3 Terms and definitions ..... 1

4 Abbreviated terms ..... 2

5 Principle ..... 2

6 Apparatus ..... 3

7 Environment for specimen preparation and measurement ..... 3

8 Calibration reference materials ..... 3

9 Safety ..... 4

10 Measurement procedure ..... 4
10.1 Preparation for measurement ..... 4
10.2 Preparing a calibration curve ..... 4
10.3 Measurement of a test specimen ..... 5

11 Expression of results ..... 5
11.1 Method of calculation ..... 5
11.2 Blank correction ..... 6

12 Precision ..... 6

13 Test report ..... 6

Annex A (informative) Reference materials ..... 8

Annex B (informative) Relative sensitivity factor ..... 9

Annex C (informative) Preparation of reference materials[6] ..... 13

Annex D (informative) VPD-TXRF method ..... 16

Annex E (informative) Glancing-angle settings ..... 18

Annex F (informative) International inter-laboratory test results ..... 22

Bibliography ..... 25